

# The 20th International Zurich Symposium on Electromagnetic Compatibility

By Dr. Pascal Leuchtman, ETH Zurich

The 20th International Zurich Symposium on Electromagnetic Compatibility (EMC Zurich 2009) was held once again at the ETH Zurich (Swiss Federal Institute of Technology) in Zurich, Switzerland, 12–16 January 2009. The symposium was staged in the central campus of the ETH, offering convenient conference facilities and easy access to the city centre. The event was organized by the Laboratory of Electromagnetic Fields and Microwave Electronics under the sponsorship of Electrosuisse and the Swiss Electromagnetics Research & Engineering Centre.

The attendance of 330 participants from 37 countries and the presence of many national and international cooperating organizations including the IEEE EMC Society, URSI, IET, as well as others, made EMC Zurich 2009 a truly international event.

The opening ceremony on Tuesday morning was led by the Co-chair of the Technical Programme Committee (TPC), Dr. Pascal Leuchtman. He expressed his best wishes to the Symposium President and General Chair, Professor Rüdiger Vahldieck, for a speedy recovery from his recent serious illness. The participants were welcomed by Mrs. Regine Aeppli (Member of Zurich Government and the Head of the Educational Department), Professor Ralph Eichler (President of ETH Zurich), Elya Joffe (President of the IEEE EMC Society), Osamu Fujiwara (Co-chairman TPC EMC Zurich 2009) and Jörg Weber (Electrosuisse). The highlight of the opening ceremony was the keynote speech given by Professor Werner Wiesbeck from the University of Karlsruhe, Germany, who spoke on “Technologies for Future Exposure Reduction.”

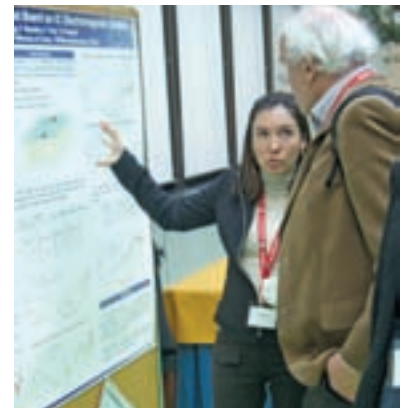
Despite the difficult economic environment, the number of papers submitted was almost at the customary level. From



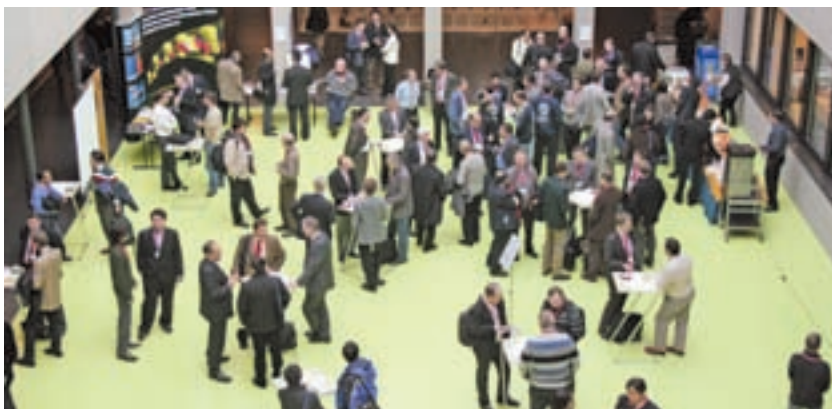
*Professor Takeo Yoshino (left) from Japan discusses a technical matter with Dr. William Radasky from Metatech in California at the workshop apéro. In the background is Professor Andrzej Sowa from the Wroclaw University of Technology.*



*Mrs. Regine Aeppli, a Member of Zurich Government, gave a speech at the Opening Ceremony.*



*Yamarita Villavicencio from the Politecnico di Torino, Italy explains her paper to Dr. Lex van Deursen from Eindhoven University, Netherlands.*



*The well attended coffee breaks provided a caffeine injection, a basket of fresh fruits and fruitful discussions.*



*Rüdiger Vahldieck, Chairman of EMC Zurich, enjoys the Opening Ceremony.*



*(From left) Flavio Canavero and Jim Muccioli joined Rebecca and Mark Steffka at the Grand Banquet. Professor Steffka from the University of Michigan – Dearborn and General Motors, gave a keynote talk at EMC Zurich titled “Automotive EMC: Practices of Today and Perspectives for the Future.”*



*(From left) Alexander Kriz of the Austrian Research Center, Bernd Deutschmann of Infineon Technologies, Elya Joffe, EMC Society President, and Jim Muccioli of X2Y Attenuators at the Blacksmith Guild Hall.*

a total of 187 submissions, 124 were accepted and presented in 25 sessions covering a broad range of areas in the field of EMC. The Technical Programme Committee was made up of 21 international experts and co-chaired by Professors Osamu Fujiwara and Pascal Leuchtman. Some 140 reviewers from all over the world did an excellent job in rating the best papers for grouping by the TPC into appropriate sessions.

The “Topical Forum” included three topical meetings with another 27 papers as well as three “Industrial Forums” focusing on the tools for numerical field simulations. These Forums completed the programme of the three main days.

On Monday and Friday of the symposium week, the five workshops, four tutorials and two technical excursions convinced a high number of participants to booking the “full registration”.

The first prize in the Student Paper contest went to The Netherlands, namely to Ousmane O. Sy from the Eindhoven University of Technology, for his paper entitled “Analysis of Stochastic Resonances in Electromagnetic Couplings to Transmission Lines.” Christian Henze from the Technical University of Dresden in Germany won the second prize for his paper entitled “Identification of Overhead Lines Using Measurements of the Electric Field Strength.” The third prize went to Thomas Demeester from the University of Ghent in Belgium for his paper entitled “Applications of the Dirichlet-to-Neumann Boundary Operator in Transmission Line Modeling.” The associated prizes were EUR 500, EUR 300 and EUR 200, respectively.

The social highlight was certainly the Symposium Banquet in the Kunsthaus Zurich with good food and excellent wine in a spectacular environment. Other social events included the workshop apéro on Monday evening, the welcome reception on Tuesday, and the “Interactive Forum Reception” on Wednesday.

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*The soul of the Zurich EMC Symposium, Barbara Schubbeck-Wagner.*



*Professor Osamu Fujiwara (left) congratulates the Best Student Paper Award winner, Ousmane Sy from the Eindhoven University of Technology.*



*Dr. Thomas Steinecke from Infinion, Germany enjoys the excellent apéro before the banquet.*



*Dr. Todd Hubing of Clemson University is shown presenting via video link; Pierre Beeckman (at left) of Philips, The Netherlands, moderated the session.*



*Bob Hofmann (left) of Hofmann EMC Engineering enjoyed dinner conversation with Flavio Canavero of the Politecnico di Torino at the Grand Banquet.*



*(From left) Professor Farbad Rachidi from the EPFL Lausanne visited with Elya Joffe, EMC Society President, and President-elect Francesca Maradei from the University of Rome "La Sapienza".*



*As they say, clothes make the man! A group gathers for the technical excursion to the world's longest tunnel.*